ELSEVIER

Thin Solid Films 359 (2000) 295–296

thin solid films

Author Index of Volume 359

Abutalibova, Z.M., 125
Adamik, M., 33
Afzal, A., 150
Agabekov, V.E., 98
Agaev, V.G., 125
Akamatsu, K., 55
Aumaille, K., 188

Bénarioua, Y., 228
Babić, R., 88
Balkenende, A.R., 1
Barna, P.B., 33
Belmonte, T., 68
Benabdesselam, M., 150
Bianco, A., 21
Bindi, R., 150
Blees, M.H., 1
Briand, D., 150
Bustamante, A.N.P., 154

Chan, Y.C., 177
Chang, J.T., 46
Chen, Y., 236
Chicot, D., 228
Chiu, S., 275
Cho, M.-H., 268
Choi, S.-H., 261
Chow, L., 154
Choy, K.L., 160
Chu, H.-S., 294
Chu, W.K., 154
Cimalla, V., 146
Czerwiec, T., 68

D'Anna, E., 141
de Bokx, P.K., 197
De Gendt, S., 197
De Tomasi, F., 251
de With, G., 210
Deki, S., 55
den Toonder, J.M.J., 1
Dultsev, F.N., 239
Dumitru, V., 17

Ecke, G., 146

Fisson, S., 171
Fredricksen, C., 154
Fu, Y., 215
Fujii, M., 55
Fujita, M., 61

Gaboriau, F., 188
Gallyamov, M.O., 98
Gergaud, P., 221
Goullet, A., 188
Granier, A., 188
Gusmano, G., 21

Hayashi, S., 55
He, J.L., 46
Hertz, D., 68
Hing, P., 215
Hong, Z.R., 14
Houssa, M., 197
Huan, C.H.A., 244
Hwang, C.-C., 294

Iacconi, P., 150
Ibragimov, N.I., 125

Jan, K.-J., 268
Jen, Y.-J., 95
Jergel, M., 141

Kaito, C., 283
Kajinami, A., 55
Kam, C.H., 177
Kido, Y., 288
Kim, H.-Y., 268
Kimura, S., 283
Kimura, Y., 283
Kira, A., 104
Kondoh, E., 255
Kullman, L., 203

Lam Loh, N., 215
Lam, Y.L., 177
Lapraz, D., 150
Lee, C.-C., 95
Lee, C.S., 14
Lee, J.-Y., 268
Lee, S.T., 14
Lee, S.-Y., 261
Lee, T.-Y., 95
Leggieri, G., 141
Leprince-Wang, Y., 171
Lesage, J., 228
Li, C., 236
Li, W.L., 14
Liang, C.J., 14
Liess, H.D., 108
Lin, S., 294
Liu, J.R., 154
Liu, M., 104
Liu, X.Y., 14
Lokhande, C.D., 136
Luby, S., 141
Luches, A., 141

Ma, Z.Q., 288
Majkova, E., 141
Makino, Y., 165
Malhotra, L.K., 28
Malzbender, J., 210
Mane, R.S., 136
Marakhtanov, A.M., 127
Marakhtanov, M.K., 127
Marian, S., 108
Martino, M., 141
Massiani, Y., 221
May, P.W., 150
Metikoš-Huković, M., 88
Michel, H., 68
Miodushevsky, P., 251
Mizuhata, M., 55
Monaghan, M.L., 197
Montesperelli, G., 21
Moon, W.S., 77
Mor, G.K., 28
Morikawa, H., 61
Morosanu, C., 17
Morten, B., 21
Murali, K.R., 113
Nakada, T., 283
Nakamura, H., 283
Nigam, T., 197
Niklasson, G.A., 203
Nilsson, H., 203
Nogi, K., 165
Nose, M., 165

Oh, S.H., 118
Oladeji, I.O., 154

Park, C.-D., 268
Park, C.G., 118
Park, C.-O., 261
Park, S.B., 77
Peng, J.B., 14
Perrone, M.R., 251
Pezoldt, J., 146
Pierson, J.F., 68
Potje-Kamloth, K., 108
Prokop, J., 39
Protopapa, M.L., 251
Prudenziati, M., 21

Que, W., 177

Rönnow, D., 203
Rego, C.A., 150
Repinsky, S.M., 239
Righini, G., 21
Rivory, J., 171
Romanus, H., 146
Roos , A., 203

Saito, Y., 283
Sandu, V., 17
Sankapal, B.R., 136
Sarkissian, A., 275
Schaefer, J.A., 146
Schulte, A.F., 154
Senderak, R., 141
Souche, D., 171
Spieb, L., 146
Staroverov, V.N., 98
Stoica, A., 17
Strømme Mattsson, M., 203
Su, B., 160
Subramanian, V., 113

PII: S0040-6090(99)01063-9

Sun, C.Q., 215
Sun, Z., 177
Sveshnikova, L.L., 239
Swaminathan, V., 113

Takai, H., 184
Takei, S., 55
Takeoka, S., 55
Terreaul, B., 275
Thomas, O., 221
Tomov, I., 33
Tsiulyanu, D., 108
Tundo, S., 251
Turban, G., 188
Turgeon, S., 275

Urbach, H.P., 197

Vacandio, F., 221
Vallée, C., 188
Vasanelli, L., 251
Veprek, S., 39
Vuye, G., 171

Wang, H., 236
Wang, J., 236
Wang, M., 82
Wang, Q., 236
Wee, A.T.S., 244
Winkelman, G.B., 1
Won, K.W., 46
Woo, S.I., 77

Yamamoto, K., 55
Yamamoto, N., 184
Yaminsky, I.V., 98
Yan, B., 215
Yang, Q., 236
Yu, J., 236
Yu, J.Q., 14
Yu-Zhang, K., 171

Zanoni, R., 21
Zhang, K., 244
Zhang, L., 82
Zhao, D., 14
Zhao, D.X., 14
Zhavnerko, G.K., 98
Zhou, M., 165
Zhou, Y., 177
Zhu, F., 244
Zybill, C.E., 39

S-

ELSEVIER

Thin Solid Films 359 (2000) 297–300

thin solid films

Subject Index of Volume 359

AlN
Stress, porosity measurements and corrosion behaviour of AlN films deposited on steel substrates, 221
Amorphous materials
The structure of thin Cr film prepared by the vacuum evaporation method, 282
Annealing
Annealing effects on the structure and mechanical properties of r.f.-sputtered Cr–B hard thin films, 165
Annealing effects
Investigation of annealing effects on indium tin oxide thin films by electron energy loss spectroscopy, 243
Atomic displacement
The atomic displacements on surface generated by low-energy projectile, 287
Atomic force microscopy
Optical and mechanical properties of TiO_2/SiO_2/organically modified silane composite films prepared by sol–gel processing, 177
Surface roughness of pyrolytic tin dioxide films evaluated by different methods, 203

Blue shift energy
A study of $Si_{1-x}Ge_x/Si$ quantum-well intermixing by photocurrent spectroscopy, 235

Cadmium sulphide
Microstructure and properties of the CdS thin films prepared by electrostatic spray assisted vapour deposition (ESAVD) method, 160
Carbides
Preparation of single phase tungsten carbide by annealing of sputtered tungsten-carbon layers, 146
Carbon
Plasma deposition of amorphous carbon films on copper, 274
CdS thin films
Comparative study of CdS thin films deposited by single, continuous, and multiple dip chemical processes, 154
Chemical bath deposition
Comparative study of CdS thin films deposited by single, continuous, and multiple dip chemical processes, 154
Chemical vapour deposition (CVD)
Thermally stimulated exoelectronic emission of CVD diamond films, 150
Chromium
The structure of thin Cr film prepared by the vacuum evaporation method, 282
Chromium borides
Annealing effects on the structure and mechanical properties of r.f.-sputtered Cr–B hard thin films, 165
Coatings
Stress, porosity measurements and corrosion behaviour of AlN films deposited on steel substrates, 221
Copper
Material characterization of Cu(Ti)–polyimide thin film stacks, 250
Oxidation, grain growth and reflow characteristics of copper thin films prepared by chemical vapor deposition, 260
Corrosion
Stress, porosity measurements and corrosion behaviour of AlN films deposited on steel substrates, 221
Cracking
Cracking and residual stress in hybrid coatings on float glass, 210

Deposition process
Microstructure and properties of the CdS thin films prepared by electrostatic spray assisted vapour deposition (ESAVD) method, 160
Investigation of annealing effects on indium tin oxide thin films by electron energy loss spectroscopy, 243
The structure of thin Cr film prepared by the vacuum evaporation method, 282
Diamond
Thermally stimulated exoelectronic emission of CVD diamond films, 150
Diamond film deposition
Control of microstructure coarsening of a Ti substrate during diamond film deposition using $Ar/H_2/CH_4$ gas mixture, 215
Diamond-like
Plasma deposition of amorphous carbon films on copper, 274
Diffusing species
Investigation of annealing effects on indium tin oxide thin films by electron energy loss spectroscopy, 243

Electrical properties
A chemical method for the deposition of Bi_2S_3 thin films from a non-aqueous bath, 136
Electrical properties and measurements
Microstructure and properties of the CdS thin films prepared by electrostatic spray assisted vapour deposition (ESAVD) method, 160
Electrical resistance

PII: S0040-6090(99)01062-7

Fine trimming of SmS film resistance by XeCl laser ablation, 256
Electrochemistry
Surface roughness of pyrolytic tin dioxide films evaluated by different methods, 203
Electron energy loss spectroscopy
Investigation of annealing effects on indium tin oxide thin films by electron energy loss spectroscopy, 243
Electron microscopy
The structure of thin Cr film prepared by the vacuum evaporation method, 282
Electronic emission
Thermally stimulated exoelectronic emission of CVD diamond films, 150
Electrophotographic layers
Electrophotographic layers of trigonal Se in the binder obtained by reduction of SeO_2 by hydrazine, 125
Electrophotographic material
Electrophotographic layers of trigonal Se in the binder obtained by reduction of SeO_2 by hydrazine, 125
Ellipsometry
Relations between the optical properties and the microstructure of TiO_2 thin films prepared by ion-assisted deposition, 171
Epitaxy
The atomic displacements on surface generated by low-energy projectile, 287
Etching
Visible luminescence from photo-chemically etched silicon, 184

Fracture toughness
Cracking and residual stress in hybrid coatings on float glass, 210

Glassy amorphous carbon
Optical and mechanical properties of TiO_2/SiO_2/organically modified silane composite films prepared by sol–gel processing, 177
Grain growth
Oxidation, grain growth and reflow characteristics of copper thin films prepared by chemical vapor deposition, 260
Grazing emission X-ray fluorescence spectrometry (GEXRF)
Characterization of silicon oxynitride films by grazing-emission X-ray fluorescence spectrometry, 197

Hard optical films
Optical and mechanical properties of TiO_2/SiO_2/organically modified silane composite films prepared by sol–gel processing, 177
Hardness
Hardness measurements of Ti and TiC multilayers: a model, 228
Hybrid organic–inorganic coatings
Cracking and residual stress in hybrid coatings on float glass, 210
Hydrazine
Electrophotographic layers of trigonal Se in the binder obtained by reduction of SeO_2 by hydrazine, 125
Hydrogenated silicon bilayer
Solid-phase crystallization of hydrogenated amorphous silicon/hydrogenated microcrystalline silicon bilayers deposited by plasma-enhanced chemical vapor deposition, 267

Immiscibility
Structure and in-depth concentrations in excimer laser irradiated Pb–Co codeposited films, 141
Indium tin oxide
Investigation of annealing effects on indium tin oxide thin films by electron energy loss spectroscopy, 243
Ion bombardment
Relations between the optical properties and the microstructure of TiO_2 thin films prepared by ion-assisted deposition, 171
The atomic displacements on surface generated by low-energy projectile, 287
Ion implantation
Plasma deposition of amorphous carbon films on copper, 274

Langmuir–Blodgett method
Preparation of conducting layers of substituted polyacetylenes by solid-phase polymerization of Langmuir–Blodgett layers, 238
Laser ablation
Fine trimming of SmS film resistance by XeCl laser ablation, 256
Laser irradiation
Structure and in-depth concentrations in excimer laser irradiated Pb–Co codeposited films, 141
Visible luminescence from photo-chemically etched silicon, 184

Metals
Electrical explosion of cold thin metal films, 127
Metallization
Preparation of single phase tungsten carbide by annealing of sputtered tungsten-carbon layers, 146
Microstructure coarsening
Control of microstructure coarsening of a Ti substrate during diamond film deposition using $Ar/H_2/CH_4$ gas mixture, 215
Models
Hardness measurements of Ti and TiC multilayers: a model, 228
Multilayers
Hardness measurements of Ti and TiC multilayers: a model, 228
Multimolecular layers
Preparation of conducting layers of substituted polyacetylenes by solid-phase polymerization of Langmuir–Blodgett layers, 238

Nanocrystal
Annealing effects on the structure and mechanical properties of r.f.-sputtered Cr–B hard thin films, 165
Nitric oxide
Characterization of silicon oxynitride films by grazing-emission X-ray fluorescence spectrometry, 197

Optical properties
A chemical method for the deposition of Bi_2S_3 thin films from a non-aqueous bath, 136

Microstructure and properties of the CdS thin films prepared by electrostatic spray assisted vapour deposition (ESAVD) method, 160
Optoelectronic devices
Investigation of annealing effects on indium tin oxide thin films by electron energy loss spectroscopy, 243
Organically modified silane
Optical and mechanical properties of TiO_2/SiO_2/organically modified silane composite films prepared by sol–gel processing, 177
Organosilicon films
A comparative study of oxygen/organosilicon plasmas and thin $SiO_xC_yH_z$ films deposited in a helicon reactor, 188
Oxidation
Oxidation, grain growth and reflow characteristics of copper thin films prepared by chemical vapor deposition, 260

Pb–Co films
Structure and in-depth concentrations in excimer laser irradiated Pb–Co codeposited films, 141
Phase transition
Preparation of single phase tungsten carbide by annealing of sputtered tungsten-carbon layers, 146
Photoacoustic deflection
Fine trimming of SmS film resistance by XeCl laser ablation, 256
Photocurrent spectroscopy
A study of $Si_{1-x}Ge_x$/Si quantum-well intermixing by photocurrent spectroscopy, 235
Photoelectronic devices
A study of $Si_{1-x}Ge_x$/Si quantum-well intermixing by photocurrent spectroscopy, 235
Photo emission
Visible luminescence from photo-chemically etched silicon, 184
Plasma-enhanced chemical vapor deposition
Solid-phase crystallization of hydrogenated amorphous silicon/hydrogenated microcrystalline silicon bilayers deposited by plasma-enhanced chemical vapor deposition, 267
Plasma processing and deposition
A comparative study of oxygen/organosilicon plasmas and thin $SiO_xC_yH_z$ films deposited in a helicon reactor, 188
Plasma deposition of amorphous carbon films on copper, 274
Polyacetylene
Preparation of conducting layers of substituted polyacetylenes by solid-phase polymerization of Langmuir–Blodgett layers, 238
Polyimide
Material characterization of Cu(Ti)–polyimide thin film stacks, 250
Polymerization
Preparation of conducting layers of substituted polyacetylenes by solid-phase polymerization of Langmuir–Blodgett layers, 238
Porosity
Stress, porosity measurements and corrosion behaviour of AlN films deposited on steel substrates, 221

Quantum well intermixing
A study of $Si_{1-x}Ge_x$/Si quantum-well intermixing by photocurrent spectroscopy, 235

Raman scattering
Optical and mechanical properties of TiO_2/SiO_2/organically modified silane composite films prepared by sol–gel processing, 177
Reflow
Oxidation, grain growth and reflow characteristics of copper thin films prepared by chemical vapor deposition, 260
Residual stress
Cracking and residual stress in hybrid coatings on float glass, 210

SiGe/Si MQW
A study of $Si_{1-x}Ge_x$/Si quantum-well intermixing by photocurrent spectroscopy, 235
Silicon
Visible luminescence from photo-chemically etched silicon, 184
Silicon oxide
A comparative study of oxygen/organosilicon plasmas and thin $SiO_xC_yH_z$ films deposited in a helicon reactor, 188
Silicon oxynitride films
Characterization of silicon oxynitride films by grazing-emission X-ray fluorescence spectrometry, 197
SmS thin films
Fine trimming of SmS film resistance by XeCl laser ablation, 256
Sol–gel technique
Optical and mechanical properties of TiO_2/SiO_2/organically modified silane composite films prepared by sol–gel processing, 177
Solid-phase crystallization
Solid-phase crystallization of hydrogenated amorphous silicon/hydrogenated microcrystalline silicon bilayers deposited by plasma-enhanced chemical vapor deposition, 267
Spin coating technique
Cracking and residual stress in hybrid coatings on float glass, 210
Sputtering
Stress, porosity measurements and corrosion behaviour of AlN films deposited on steel substrates, 221
Stress measurement
Stress, porosity measurements and corrosion behaviour of AlN films deposited on steel substrates, 221
Structural properties
Electrical explosion of cold thin metal films, 127
Surface defects
The atomic displacements on surface generated by low-energy projectile, 287
Surface morphology
Thermally stimulated exoelectronic emission of CVD diamond films, 150
Surface roughness
Surface roughness of pyrolytic tin dioxide films evaluated by different methods, 203
Surface segregation

Structure and in-depth concentrations in excimer laser irradiated Pb–Co codeposited films, 141
Thin film
A chemical method for the deposition of Bi_2S_3 thin films from a non-aqueous bath, 136
Annealing effects on the structure and mechanical properties of r.f.-sputtered Cr–B hard thin films, 165
Thin film stacks
Material characterization of Cu(Ti)–polyimide thin film stacks, 250
Tin dioxide
Surface roughness of pyrolytic tin dioxide films evaluated by different methods, 203
Titanium
Material characterization of Cu(Ti)–polyimide thin film stacks, 250
Titanium carbide
Hardness measurements of Ti and TiC multilayers: a model, 228
Titanium dioxide
Relations between the optical properties and the microstructure of TiO_2 thin films prepared by ion-assisted deposition, 171
Ti substrate
Control of microstructure coarsening of a Ti substrate during diamond film deposition using $Ar/H_2/CH_4$ gas mixture, 215
Transmission electron microscopy
Relations between the optical properties and the microstructure of TiO_2 thin films prepared by ion-assisted deposition, 171
Trigonal Se
Electrophotographic layers of trigonal Se in the binder obtained by reduction of SeO_2 by hydrazine, 125
Tungsten
Preparation of single phase tungsten carbide by annealing of sputtered tungsten-carbon layers, 146